

In the Claims:

Please cancel claims 45-56 without prejudice.

Please add the following new claims 64-110 as follows:

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52 64. (New) An exposure apparatus that transfers an image set movably by a stage assembly onto a device utilizing a beam of light, the exposure apparatus being adapted to be mounted to a mounting base, the exposure apparatus comprising:

a base assembly that includes at least a portion of the stage assembly;

a base isolation system that secures the base assembly to the mounting base, the base isolation system reducing the effect of vibration of the mounting base causing vibration on the base assembly;

an optical assembly that includes an optical frame, an optical device and a stage base, the optical device directs the beam of light and the stage base supports a portion of the stage assembly, the optical frame including a center frame and a first upper base mount that supports the stage base; and

an optical isolation system that secures the optical assembly to the base assembly, the optical isolation system including a first support that is secured to the center frame, the optical isolation system reducing the effect of vibration of the base assembly causing vibration on at least one of the optical assembly and the optical device, wherein the first support and a proximal section of the first upper base mount are substantially aligned along a first Z axis.

53 65. (New) The exposure apparatus of claim 64 wherein the base isolation system and the optical isolation system are at approximately the same height along a Z axis. 52

54 66. (New) The exposure apparatus of claim 64 wherein the optical frame includes a second upper base mount that supports the stage base, wherein the optical isolation system includes a second support that is secured to the center frame, and 52

wherein a proximal section of the second upper base mount and the second support are substantially aligned along a second Z axis.

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57. (New) The exposure apparatus of claim 56 wherein the optical frame includes a third upper base mount that supports the stage base, wherein the optical isolation system includes a third support that is secured to the center frame, and wherein a proximal section of the third upper base mount and the third support are substantially aligned along a third Z axis.

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58. (New) The exposure apparatus of claim 54 wherein the optical isolation system includes a first assembly mover that adjusts the position of the optical assembly relative to the base assembly, the first assembly mover being substantially positioned along the first Z axis.

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59. (New) The exposure apparatus of claim 54 wherein the optical assembly further comprises a sensor column including a first sensor mount that secures the sensor column to the optical frame, the first sensor mount being substantially positioned along the first Z axis.

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70. (New) The exposure apparatus of claim 59 wherein the sensor column includes a second sensor mount that secures the sensor column to the optical frame, and the optical isolation system includes a second support, wherein the second sensor mount and the second support are positioned substantially along a second Z axis.

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71. (New) The exposure apparatus of claim 70 wherein the sensor column includes a third sensor mount that secures the sensor column to the optical frame, and the optical isolation system includes a third support, wherein the third sensor mount and the third support are positioned substantially along a third Z axis.

60 72. (New) The exposure apparatus of claim ~~64~~ 52 wherein the base assembly further includes a base frame and a portion of a second stage assembly, wherein the stage assembly and the second stage assembly are at least partly supported by the base frame.

61 73. (New) The exposure apparatus of claim 72 60 wherein the base assembly further includes a first enclosure that substantially encircles the stage assembly and a second enclosure that substantially encircles the second stage assembly.

62 74. (New) The exposure apparatus of claim ~~64~~ 52 wherein the base assembly defines a frame aperture and wherein a portion of the optical assembly extends into the frame aperture.

63 75. (New) A device manufactured with the exposure apparatus according to claim ~~64~~ 52

64 76. (New) A wafer on which an image has been formed by the exposure apparatus of claim ~~64~~ 52

65 77. (New) An exposure apparatus that transfers an image set movably by a stage assembly onto a device utilizing a beam of light, the exposure apparatus being adapted to be mounted to a mounting base, the exposure apparatus comprising:

a base assembly that includes at least a portion of the stage assembly;

an optical assembly that includes an optical frame, an optical device and a stage base, the optical device directs the beam of light and the stage base supports a portion of the stage assembly, the optical frame including a center frame, a first upper base mount that supports the stage base, a second upper base mount that supports the stage base, and a third upper base mount that supports the stage base; and

an optical isolation system that secures the optical assembly to the base assembly, the optical isolation system including a first support that is secured to the center frame, a second support that is secured to the center frame and a third support that is secured to the center frame, the optical isolation system reducing the effect of vibration of the base assembly causing vibration on at least one of the optical assembly and the optical device, wherein the first support and a proximal section of the first upper base mount are substantially aligned along a first Z axis, wherein the second support and a proximal section of the second upper base mount are substantially aligned along a second Z axis, and wherein the third support and a proximal section of the third upper base mount are substantially aligned along a third Z axis.

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78. (New) The exposure apparatus of claim 77 further comprising a base isolation system that secures the base assembly to the mounting base, the base isolation system reducing the effect of vibration of the mounting base causing vibration on the base assembly.

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79. (New) The exposure apparatus of claim 77 wherein the optical isolation system includes a first assembly mover that adjusts the position of the optical assembly relative to the base assembly, the first assembly mover being substantially positioned along the first Z axis.

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80. (New) The exposure apparatus of claim 77 wherein the optical assembly further comprises a sensor column including a first sensor mount that secures the sensor column to the optical frame, a second sensor mount that secures the sensor column to the optical frame and a third sensor mount that secures the sensor column to the optical frame, the first sensor mount being substantially positioned along the first Z axis, the second sensor mount being substantially positioned along the second Z axis, and the third sensor mount being substantially positioned along the third Z axis.

69 81. (New) The exposure apparatus of claim 77<sup>65</sup> wherein the base assembly further includes a base frame and a portion of a second stage assembly, wherein the stage assembly and the second stage assembly are at least partly supported by the base frame.

70 82. (New) The exposure apparatus of claim 81<sup>69</sup> wherein the base assembly further includes a first enclosure that substantially encircles the stage assembly and a second enclosure that substantially encircles the second stage assembly.

71 83. (New) The exposure apparatus of claim 77<sup>65</sup> wherein the base assembly defines a frame aperture and wherein a portion of the optical assembly extends into the frame aperture.

72 84. (New) A device manufactured with the exposure apparatus according to claim 77<sup>65</sup>

73 85. (New) A wafer on which an image has been formed by the exposure apparatus of claim 77<sup>65</sup>

74 86. (New) An exposure apparatus that transfers an image set movably by a stage assembly onto a device utilizing a beam of light, the exposure apparatus being adapted to be mounted to a mounting base, the exposure apparatus comprising:

a base assembly that includes at least a portion of the stage assembly;

an optical assembly that includes an optical frame, an optical device, a stage base and a sensor column, the optical device directs the beam of light and the stage base supports a portion of the stage assembly, the optical frame including a center frame and a first upper base mount that supports the stage base, the sensor column including a first sensor mount that secures the sensor column to the optical frame; and

an optical isolation system that secures the optical assembly to the base assembly, the optical isolation system including a first support that is secured to the center frame, the optical isolation system reducing the effect of vibration of the base assembly causing vibration on at least one of the optical assembly and the optical device, wherein the first support, a proximal section of the first upper base mount and the first sensor mount are substantially aligned along a first Z axis.

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87. (New) The exposure apparatus of claim 74 further comprising a base isolation system that secures the base assembly to the mounting base, the base isolation system reducing the effect of vibration of the mounting base causing vibration on the base assembly, the base isolation system and the optical isolation system being at approximately the same height along a Z axis.

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88. (New) The exposure apparatus of claim 74 wherein the optical frame includes a second upper base mount that supports the stage base, wherein the optical isolation system includes a second support that is secured to the center frame, and wherein a proximal section of the second upper base mount and the second support are substantially aligned along a second Z axis.

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89. (New) The exposure apparatus of claim 76 wherein the optical frame includes a third upper base mount that supports the stage base, wherein the optical isolation system includes a third support that is secured to the center frame, and wherein a proximal section of the third upper base mount and the third support are substantially aligned along a third Z axis.

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90. (New) The exposure apparatus of claim 74 wherein the optical isolation system includes a first assembly mover that adjusts the position of the optical assembly relative to the base assembly, the first assembly mover being substantially positioned along the first Z axis.

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81. (New) The exposure apparatus of claim ~~80~~ <sup>74</sup> wherein the sensor column includes a second sensor mount that secures the sensor column to the optical frame, and the optical isolation system includes a second support, wherein the second sensor mount and the second support are positioned substantially along a second Z axis.

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82. (New) The exposure apparatus of claim ~~91~~ <sup>79</sup> wherein the sensor column includes a third sensor mount that secures the sensor column to the optical frame, and the optical isolation system includes a third support, wherein the third sensor mount and the third support are positioned substantially along a third Z axis.

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83. (New) The exposure apparatus of claim ~~86~~ <sup>74</sup> wherein the base assembly further includes a base frame and a portion of a second stage assembly, wherein the stage assembly and the second stage assembly are at least partly supported by the base frame.

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84. (New) The exposure apparatus of claim ~~93~~ <sup>81</sup> wherein the base assembly further includes a first enclosure that substantially encircles the stage assembly and a second enclosure that substantially encircles the second stage assembly.

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85. (New) The exposure apparatus of claim ~~86~~ <sup>74</sup> wherein the base assembly defines a frame aperture and wherein a portion of the optical assembly extends into the frame aperture.

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86. (New) A device manufactured with the exposure apparatus according to claim ~~86~~ <sup>74</sup>

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87. (New) A wafer on which an image has been formed by the exposure apparatus of claim ~~86~~ <sup>74</sup>

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86 98. (New) An exposure apparatus that transfers an image set movably by a stage assembly onto a device utilizing a beam of light, the exposure apparatus being adapted to be mounted to a mounting base, the exposure apparatus comprising:

an optical assembly that includes an optical frame, an optical device and a stage base, the optical device directs the beam of light and the stage base supports a portion of the stage assembly, the optical frame including a center frame and a first upper base mount that supports the stage base;

a base assembly that includes a base frame and at least a portion of the stage assembly, the base frame defining a frame aperture that is sized and shaped to receive a portion of the optical assembly; and

an optical isolation system that secures the optical assembly to the base assembly, the optical isolation system including a first support that is secured to the center frame, the optical isolation system reducing the effect of vibration of the base assembly causing vibration on at least one of the optical assembly and the optical device, wherein the first support and a proximal section of the first upper base mount are substantially aligned along a first Z axis.

87 99. (New) The exposure apparatus of claim 86 wherein the optical frame fits within the frame aperture of the base frame, and wherein the optical frame is secured to the optical device.

88 100. (New) The exposure apparatus of claim 86 further comprising a base isolation system that secures the base assembly to the mounting base, the base isolation system reducing the effect of vibration of the mounting base causing vibration on the base assembly, the base isolation system and the optical isolation system being at approximately the same height along a Z axis.

89 101. (New) The exposure apparatus of claim 86 wherein the optical frame includes a second upper base mount that supports the stage base, wherein the optical isolation system includes a second support that is secured to the center frame, and



wherein a proximal section of the second upper base mount and the second support are substantially aligned along a second Z axis.

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102. (New) The exposure apparatus of claim 101<sup>89</sup> wherein the optical frame includes a third upper base mount that supports the stage base, wherein the optical isolation system includes a third support that is secured to the center frame, and wherein a proximal section of the third upper base mount and the third support are substantially aligned along a third Z axis.

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103. (New) The exposure apparatus of claim 98<sup>86</sup> wherein the optical isolation system includes a first assembly mover that adjusts the position of the optical assembly relative to the base assembly, the first assembly mover being substantially positioned along the first Z axis.

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104. (New) The exposure apparatus of claim 98<sup>86</sup> wherein the optical assembly further comprises a sensor column including a first sensor mount that secures the sensor column to the optical frame, the first sensor mount being substantially positioned along the first Z axis.

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105. (New) The exposure apparatus of claim 104<sup>92</sup> wherein the sensor column includes a second sensor mount that secures the sensor column to the optical frame, and the optical isolation system includes a second support, wherein the second sensor mount and the second support are positioned substantially along a second Z axis.

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106. (New) The exposure apparatus of claim 105<sup>93</sup> wherein the sensor column includes a third sensor mount that secures the sensor column to the optical frame, and the optical isolation system includes a third support, wherein the third sensor mount and the third support are positioned substantially along a third Z axis.

95 107. (New) The exposure apparatus of claim 98<sup>86</sup> wherein the base assembly further includes a base frame and a portion of a second stage assembly, wherein the stage assembly and the second stage assembly are at least partly supported by the base frame.

96 108. (New) The exposure apparatus of claim 107<sup>95</sup> wherein the base assembly further includes a first enclosure that substantially encircles the stage assembly and a second enclosure that substantially encircles the second stage assembly.

97 109. (New) A device manufactured with the exposure apparatus according to claim 98<sup>86</sup>.

98 110. (New) A wafer on which an image has been formed by the exposure apparatus of claim 98<sup>86</sup>.